Title (en)

A heat mode sensitive imaging element for making positive working printing plates

Title (de)

Wärmeempfindliches Aufzeichnungsmaterial zur Herstellung von positiv arbeitenden Druckplatten

Title (fr)

Matériau d'enregistrement thermosensible pour la fabrication de plaques d'impression positives

Publication

EP 0950513 A1 19991020 (EN)

Application

EP 98201216 A 19980415

Priority

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Abstract (en)

According to the present invention there is provided a heat mode imaging element for making a lithographic printing plate having on a lithographic base with a hydrophilic surface a first layer including a polymer soluble in an aqueous alkaline solution, and a top layer on the same side of the lithographic base as the first layer that is IR-sensitive and unpenetrable for an aqueous alkaline developer wherein said first layer and said top layer may be one and the same layer; characterized in that the surface of said element upon exposure and treatment with an aqueous alkaline developer is such that a) the contact angle between the unexposed areas of the imaging element and the aqueous alkaline developer changes for at most 6 DEG during the first minute of contact with said developer; b) the contact angle between the exposed areas of the imaging element and the aqueous alkaline developer changes more than 15 DEG during the first minute of contact with said developer; c) the difference in contact angle between on the one side the unexposed areas and on the other side the exposed areas of the imaging element with the aqueous alkaline solution at the onset of the measurement is not higher than 10 DEG .

IPC 1-7

B41C 1/10; B41M 5/36

IPC 8 full level

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CPC (source: EP)

B41C 1/1016 (2013.01); B41C 2210/02 (2013.01); B41C 2210/06 (2013.01); B41C 2210/14 (2013.01); B41C 2210/22 (2013.01); B41C 2210/24 (2013.01); B41C 2210/262 (2013.01)

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